



Features

Temperature range: 50°C to 600°C
Crucible: 15cc Alumina
Charge Capacity: 10cc
Typical LTE 10 rates (300mm Throw Distance):
AlQ3: 50
PTCDA: 0.2 to 2.0 Å/sec
CuPc: 0.2 to 2.0 Å/sec
C60: 0.2 to 2.0 Å/sec

Functionality

Our low temperature evaporator (LTE) deposits volatile organic materials for thin film formation needed to produce organic light emitting devices (OLEDs), photovoltaic cells, and other organic material-based devices. It can also be used for low temperature metal films where repeatability, stability and uniform films are required.

PID temperature control and uniform SCR-based power output using our M.A.P.S. power supplies and KJLC's eKlipse software package enables precise deposition rate control and ensures a high-quality, uniform films. The "plug-in" source facilitates easy removal of the material for replenishment. The Thermocouple is in contact with the crucible base for accurate temperature readings. Every LTE source is installed with an integral flip shutter.

The Optimum plume configuration distributes material evenly across the substrate, producing films with 5% uniformity on a 6" (150mm) substrate at > 5 Å/sec. The Efficient heater coil provides an optimum heating profile allowing for low temperature operation (50° C to 600° C) with PID control of (±0.1° C).

Where Used: PRO Line PVD 75

Recommended Applications: Insulating or conductive films, Co depositions

Recommended Maintenance: Cleaning of dark space shields and target changes

**Power is limited by target thermal conductivity, coolant flow, target melting point, coolant inlet temperature, and target cooling method (direct cooled / indirect cooled). The limits stated here are guidelines only. Certain target materials cannot run at these values (insulating and refractory metals). Some materials can be run at higher powers (good thermal conducting, metal targets).*